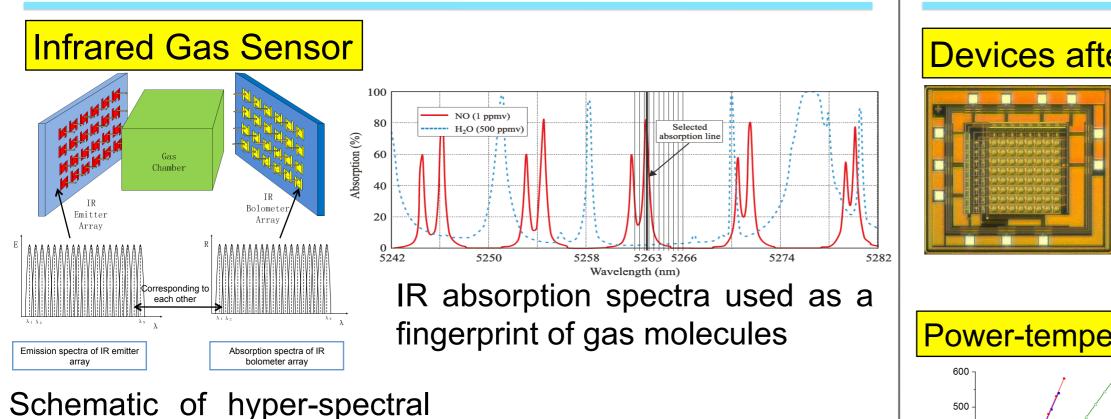


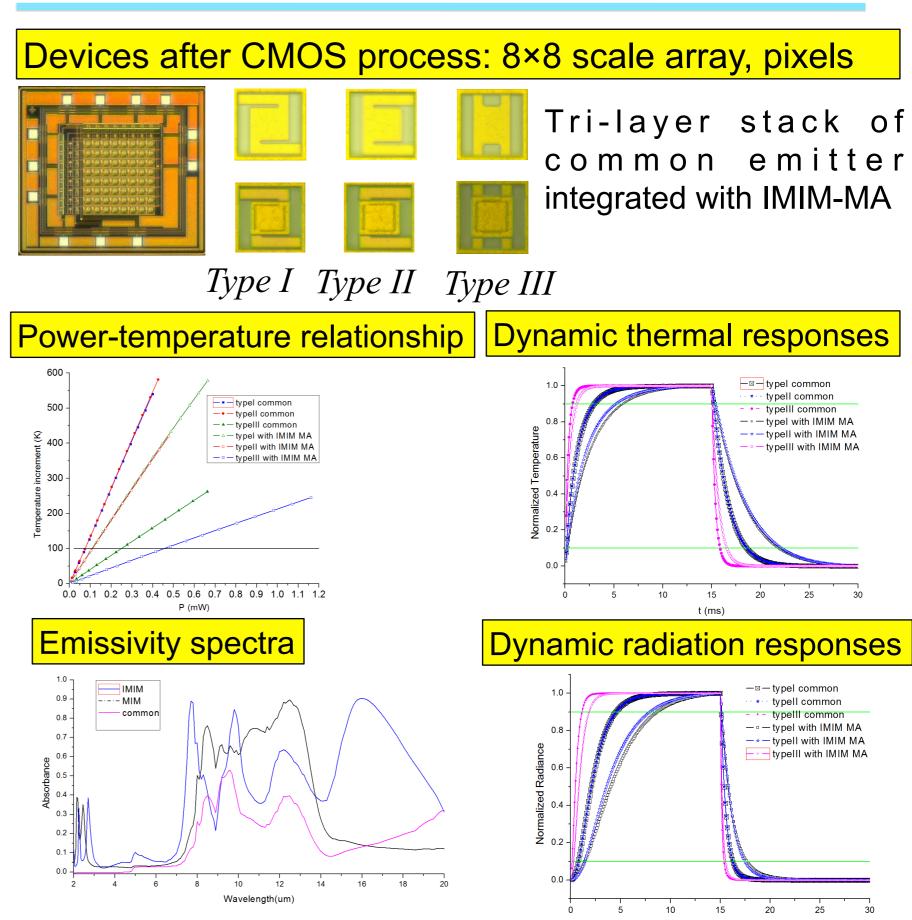
Design of CMOS-MEMS Infrared Emitter Arrays Cheng Zhengxi and Hiroshi Toshiyoshi

We present a new design of CMOS-MEMS broadband infrared (IR) emitter arrays with metamaterial absorbers (MAs) integrated by the CMOS back-end of line (BEOL) process of 0.5 µm 2-Poly-3-Metal CMOS rules. Three different shapes of micro emitters are designed to balance the trade-off relationship between performance and yield. Tri-layer metal-insulator-metal (MIM) and four-layer insulator-metal-insulator-metal (IMIM) MAs are adopted to broaden the emissivity waveband and to enhance the emissivity.

Introduction



Result

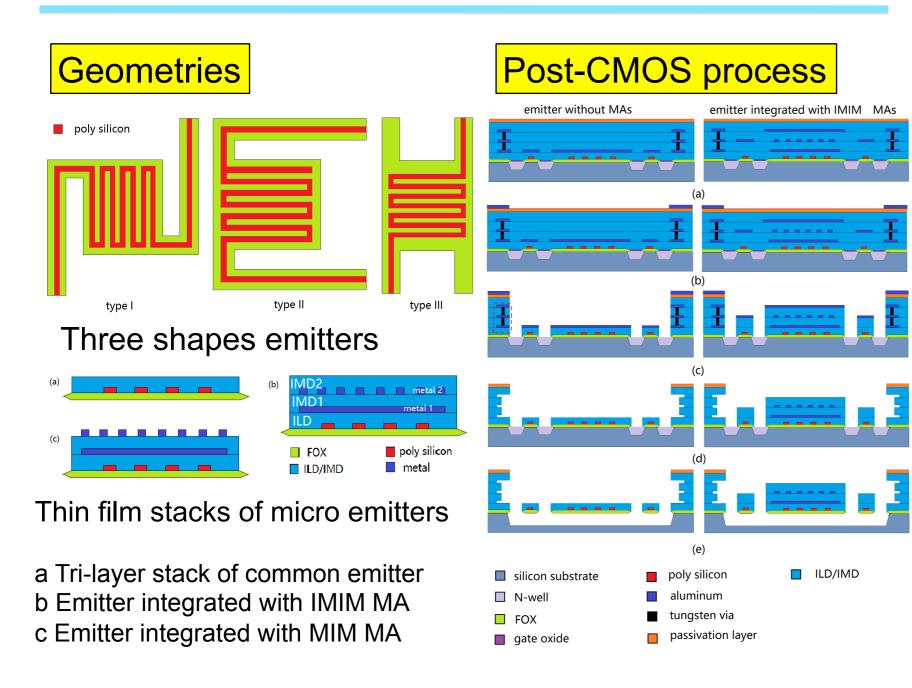


IR gas sensor structure

Objectives of design: MEMS IR emitter

For high IR emissivity, we use metamaterial absorbers integrated by CMOS back end of line (BEOL) process on the top of CMOS MEMS **IR** emitters

Process



Cheng Zhengxi and Hiroshi Toshiyoshi: "A design of integrated CMOS-MEMS infrared emitter arrays," IEICE Electronics Express, Vol. 13 No. 7 pp. 1-10 (2016).

Table 1: Thermal properties and radiation properties of IR emitters

Emitters	Thermal Conductance (10 ⁻⁶ W/K)	Thermal Mass (10 ⁻⁹ J/K)	Thermal Time Constant (ms)	Radiance Rise Time (ms)	Radiance Fall Time (ms)	Power for per K temperature increment (10 ⁻⁶ W/K)
Type I common	0.74	1.06	1.43	3.8	2.6	0.74
Type II common	0.74	1.07	1.45	3.8	2.6	0.73
Type III common	2.48	0.90	0.35	1.2	1.0	2.51
Type I with IMIM	1.10	3.11	2.82	8.3	2.4	1.14
Type II with IMIM	1.11	3.06	2.76	7.5	2.2	1.13
Type III with IMIM	4.54	2.74	0.60	1.6	1.3	4.66

Conclusion

CMOS-MEMS broadband IR emitter arrays integrated with MAs are designed by using CSMC 0.5 µm CMOS process. Thermal radiation simulation results show that Type-III common IR emitters and Type-III emitter with IMIM-MA function upwards of 454 Hz and 344 Hz. Simulated absorption spectra show that MIM-MAs and IMIM-MAs enhance IR absorbance in 2-3 µm waveband, and broaden the IR absorption to 20 µm.

Cheng, Z., and Toshiyoshi, H.: 'Design of CMOS-MEMS Infrared Emitter Arrays'. Proc. 11th Annual IEEE International Conference on Nano/Micro Engineered and Molecular Systems (IEEE-NEMS 2016), Matsushima and Sendai, Japan, 17-20 April, 2016



